

ION IMPLANTATION SERVICES

Ion Implant Capabilities

- Wafer sizes 2" through 300mm
- Energy as low as 1keV (Boron, Phosphorous, Beryllium, etc.)
- Energy as high as 400keV (B, P, As, Be, H, He, Si, Ge, etc.)
- Heated and Cooled implants from (-120°C to 600°C) for 2" to 6" wafers
- Over 75 implantation species available for production and R&D
- High tilt angles up to 89° and wafer orientation within 1°
- Custom wheel and platen design for non-wafer substrates as well as double-sided implants

Species List

Species currently available for Ion Implantation
(Additional species available on request)

Ag	Co	He	¹⁵ N	³⁰ Si
Al	Cr	Hf	N ₂ *	Se
Ar	Cs	Hg	Na	Sn
As	Cu	Ho	Nb	Sr
B	D	I	Ne	Ta
BF ₂	D ₂	In	Ni	Te
Ba	Er	Ir	¹⁸ O	Ti
Be	Eu	K	¹⁸ O	Tl
Bi	F	Kr	O ₂ *	V
Br	Fe	La	P	W
¹² C	Ga	Li	Pb	Xe
¹³ C	Ge	Mg	S	Y
Ca	Gd	Mn	Sb	Yb
Ce	H	Mo	²⁸ Si	Zn
Cl	H ₂	¹⁴ N	²⁹ Si	Zr

Periodic Table of Elements

Legend:

- Routine
- Engineering
- Experimental
- Special Setup
- Developmental
- Radioactive

* Lanthanides
** Actinides

*Either isotope

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